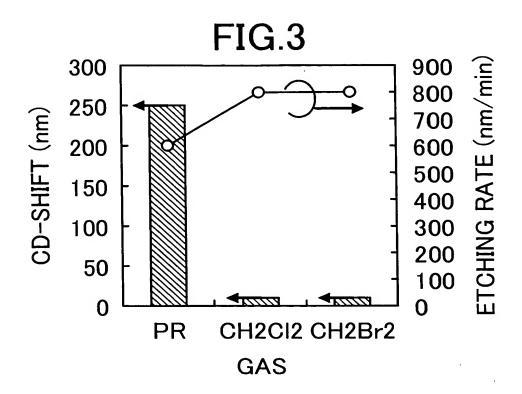
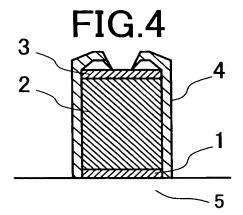


GAS	INFLAMMABILITY	OZONELAYER DESTRUCTIVILITY	CARCINOGENICITY	PARTICLE CONTAMINATION	PROTECTION FILM REMOVABILITY
CCI4	NO	YES	NO	ĹOW	GOOD
СНСІЗ	NO	NO	YES	LOW	GOOD
CH2CI2	NO	NO	NO	LOW	GOOD
СНЗСІ	EXPLOSIVE IN AIR	NO	NO	LOW	GOOD
C2H2CI2	EXPLOSIVE	NO	NO	LOW	GOOD
C2H5CI	EXPLOSIVE	NO	NO	LOW	GOOD
C3H6Cl2	EXPLOSIVE	NO	NO	LOW	GOOD
СхНу	EXPLOSIVE	NO	NO	LOW	GOOD
CxHyFz	NO	PARTLY YES	NO	HIGH	GOOD
CxHyBrz	PARTLY YES	NO	NO	LOW	NG
N2	NO	NO	NO	HIGH	NG

FIG.2 FAILURE BY PARTICLE CONTAMINATION 1.2 CH2Cl2,CH2Br2 CHF3 N2 PR 8.0 0.6 0.4 0.2 0 5 2 3 4 0 6 NUMBER OF WAFER (x1000)





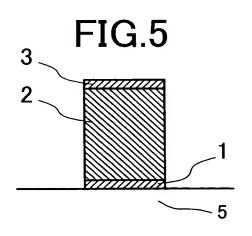


FIG.6

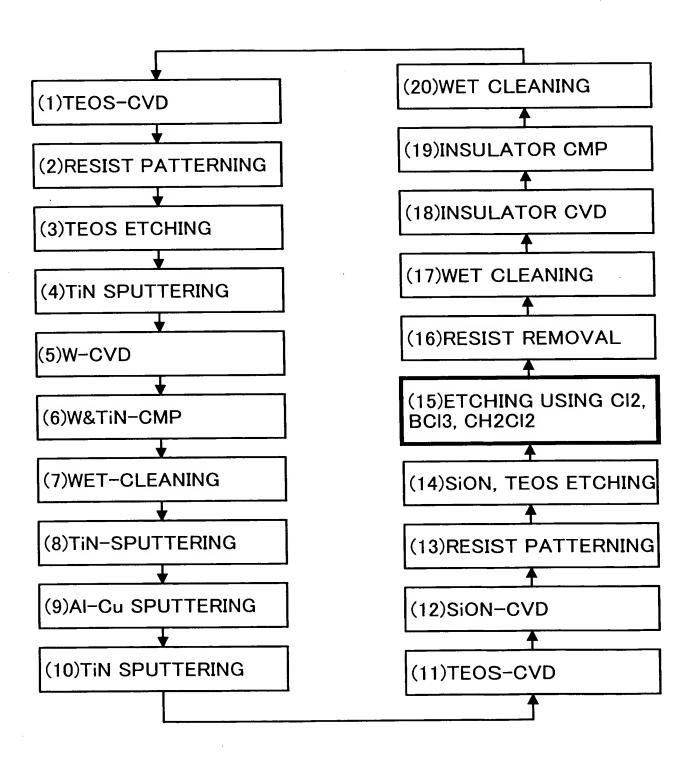


FIG.7A

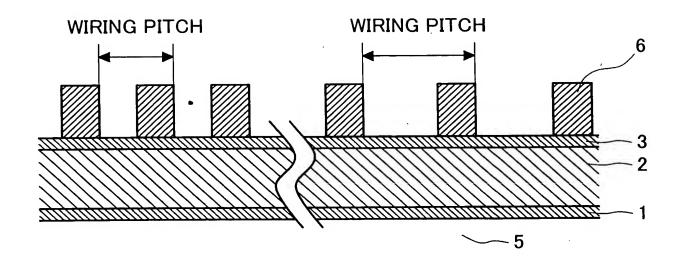


FIG.7B

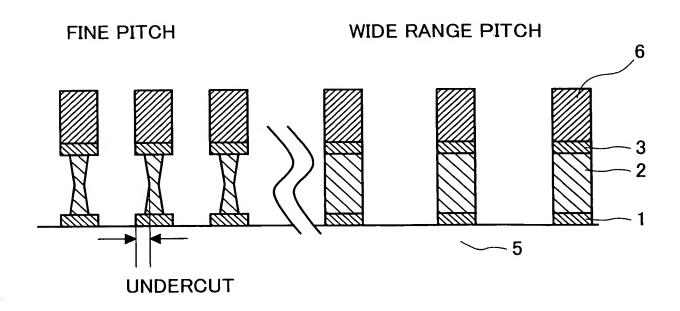


FIG.8

WIRING	UNDERCUTTING CONDITION			
PITCH (nm)	PR GAS ADDITION	CH2CI2 GAS ADDITION		
1000	NO-UNDERCUT	NO-UNDERCUT		
500	NO-UNDERCUT	NO-UNDERCUT		
300	UNDERCUT	NO-UNDERCUT		
260	UNDERCUT	NO-UNDERCUT		
200	UNDERCUT	NO-UNDERCUT		

FIG.9

